



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 10/655,997
Filing Date September 5, 2003
Confirmation No. 7524
Inventor Jon P. Daley
Assignee Micron Technology, Inc.
Group Art Unit 2822
Examiner Pamela E. Perkins
Attorney's Docket No. MI22-2380
Customer No. 021567
Title: Methods of Forming Patterned Photoresist Layers Over Semiconductor
Substrates

Fee only

RESPONSE TO MARCH 11, 2005 OFFICE ACTION

To: Mail Stop Amendment
Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

VIA U.S. EXPRESS MAIL

From: Mark Matkin (Tel. 509-624-4276; Fax 509-838-3424)
Wells St. John P.S.
601 West First Avenue, Suite 1300
Spokane, WA 99201-3828

Responsive to the Office Action dated March 11, 2005, Applicant amends and remarks as follows:

AMENDMENTS

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Thereby, the opposite of what Applicant claims, namely increased footing, occurs by the Duval treatment. Therefore, Applicant's independent claims 30 and 53 recite something which is not found within the teachings of Duval, and the anticipation rejection must be withdrawn for this reason. Action to that end is requested.

Applicant's dependent claims should be allowed as depending from allowable base claims, and for their own recited features which are neither shown nor suggested in the cited art. Action to that end is requested.

Respectfully submitted,

Dated: 6-2-05

By: 
Mark S. Matkin
Reg. No. 32,268